

WHAT IS CLAIMED IS:

*add A'*

1. A negative-working photosensitive resin composition comprising (A) a film-forming polymer, (B) an unsaturated compound having a radical polymerizable ethylenic double bond, (C) a photopolymerization initiator, and (D) a thermal polymerization inhibitor, wherein said resin composition further contains (E) at least one member selected from compounds represented by following formula (I):



wherein -X represents -OR<sup>2</sup>, -COOH, -SO<sub>3</sub>H, -CONHR<sup>2</sup>, -COR<sup>2</sup>, -SO<sub>2</sub>NHR<sup>2</sup>, -HNCONHR<sup>2</sup>, or -HNCOOR<sup>2</sup>; R<sup>1</sup> and R<sup>2</sup>, which may be the same or different, each represents a hydrogen atom, a substituted or unsubstituted, saturated or unsaturated hydrocarbon group, provided that it does not contain a radical polymerizable ethylenic double bond, a substituted or unsubstituted alicyclic hydrocarbon group, a substituted or unsubstituted aromatic hydrocarbon group, or a heterocyclic group; they may have an ether bond in the chain, provided that when -X is -OH, then R<sup>1</sup> represents a group other than a hydrogen atom and an aromatic hydrocarbon group, in a range of from 0.001 to 0.3% by weight based on the weight of the photosensitive resin composition.

2. A negative photosensitive resin composition as claimed in claim 1, wherein the compound represented by the formula (I) has a boiling point of at least 95°C.

3. A negative photosensitive resin composition as claimed in claim 1, wherein the component (A) is at least one member selected

from water-soluble polymers, alkali-soluble polymers, and alcohol-soluble polymers.

4. A photosensitive resin plate comprising a support having formed thereon a photosensitive layer comprising the negative-working photosensitive resin composition as claimed in claim 1 directly or via an adhesive layer.

5. A photosensitive resin plate having formed thereon photocured images obtained by selectively exposing the photosensitive layer on the photosensitive resin plate as claimed in claim 4 through a mask pattern, developing, and forming the photocured images by removing the unexposed areas.